### **SLIDES ON DELAMINATION MECHANICS**

with applications to films, coatings & multilayers



#### BASIC ELASTICITY SOLUTION FOR INFINITE ELASTIC BILAYER WITH SEMI-INFINITE CRACK

Equilibrated loads. General solution for energy release rate and stress intensity factors available in Suo and Hutchinson (1990)



If both materials incompressible:  $\beta_D = 0$ For homogeneous case:  $\alpha_D = \beta_D = 0$  $\alpha_{\rm D}$  is the more important of the two parameters for most bilayer crack problems Take  $\beta_D = 0$  if you can. It makes life easier!

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#### **Basic solution continued:**

**Energy release rate** 

$$G = \frac{1}{2\overline{E}_1} \left( \frac{P^2}{d} + 12\frac{M^2}{d^3} \right)$$
$$\overline{E} = E/(1-\nu^2)$$

Stress intensity factors:  $(\beta_D = 0)$ (see Hutchinson & Suo (1992) if second Dundurs' parameter cannot be taken to be zero)

$$K_{I} = \frac{1}{\sqrt{2}} \left[ P d^{-1/2} \cos \omega + 2\sqrt{3} M d^{-3/2} \sin \omega \right]$$
$$K_{II} = \frac{1}{\sqrt{2}} \left[ P d^{-1/2} \sin \omega - 2\sqrt{3} M d^{-3/2} \cos \omega \right]$$

where  $\omega(\alpha_D)$  is shown as a plot and is tabulated in Suo & Hutch. Note: For any interface crack between two isotropic materials,

$$G = \frac{1 - \beta_D^2}{2} \left( \frac{1}{\overline{E}_1} + \frac{1}{\overline{E}_2} \right) \left( K_I^2 + K_{II}^2 \right)$$





$$P = \int_0^h \sigma(y) dy$$
$$M = \int_0^h \sigma(y) (y - \frac{1}{2}h) dy$$

Pre-stress can arise from thermal expansion mismatch, deposition processes, mechanical loading (bending or stretching of film/substrate), drying or absorption of moisture, etc.

**Simplest example:** uniformly stressed film on an interface with no mismatch

$$P = \sigma h, \ M = 0, \ \omega = 52.1^{\circ},$$
  

$$G = \sigma^{2} h / 2\overline{E} \qquad \sigma > 0: \quad K_{I} = 0.434 \sigma \sqrt{h}, \quad K_{II} = 0.556 \sigma \sqrt{h}$$
  

$$\sigma < 0: \quad K_{I} = 0, \quad K_{II} = -0.707 \sigma \sqrt{h}$$

Closed, mode II crack. Only valid if friction is neglected.

#### Application to films & coatings, continued: Role of elastic mismatch

**Illustrative example:** uniformly stressed film: tension

$$P = \sigma h, \ M = 0, \ \sigma > 0: \ K_I = \sigma \sqrt{h} \cos \omega / \sqrt{2}, \ K_{II} = \sigma \sqrt{h} \sin \omega / \sqrt{2}$$
  
Energy release rate:  $G = \sigma^2 h / 2\overline{E}$ , Measure of mode mix:  $\psi = \tan^{-1}(K_{II} / K_I)$ 



For modest mismatches (metals on metals or ceramics), the role of the elastic mismatch on the mode mix is relatively minor. However, for large mismatches (e.g., metals or ceramics on polymers or elastomers, or vise versa), the influence on the mode mix can be large. But note that the mismatch does not effect the energy release rate for long cracks (steady-state).



#### Mode I cracking in substrate driven by tensile stresses in film or coating

The solution to the problem depicted is given in Suo & Hutch (1989) for general elastic mismatch between the top layer and the substrate. See Drory, Thouless & Evans (1988) for *C* experimental observations for metal/glass systems.

#### Neglecting elastic mismatch the basic solution gives

$$K_{I} = \frac{\sigma h}{\sqrt{2d}} \left( \cos \omega + \sqrt{3} \left( (d-h)/d \right) \sin \omega \right)$$
$$K_{II} = \frac{\sigma h}{\sqrt{2d}} \left( \sin \omega - \sqrt{3} \left( (d-h)/d \right) \cos \omega \right)$$



#### Depth of mode I crack

$$K_{II} = 0$$
 with  $\omega = 52.1^{\circ} \Rightarrow \frac{d}{h} = 3.86$ ,  $K_I = 0.586 \sigma \sqrt{h}$  and  $G = 0.343 \sigma^2 h / \overline{E}$ 

Compare with mixed mode delamination along interface

$$K_I = 0.434 \sigma \sqrt{h}, K_I = 0.556 \sigma \sqrt{h}$$
 and  $G = 0.50 \sigma^2 h / \overline{E}$ 

Substrate delamination as mode I crack propagation is observed in systems where the interface is relatively tough and the substrate is brittle. The stress in the film or coating must be in tension. No mode I path exists in the substrate if the stress is compression.



For a mode I crack to exist within layer with linear stress variation:

$$\sigma_0 > 0 \quad \& \qquad \implies \qquad d = 0.817 \frac{\sigma_0}{d\sigma/dy} \& \qquad G = 0.353 \frac{\sigma_0}{\overline{E} \, d\sigma/dy}$$

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#### **Delamination of an Interior Interface Crack in a Thermal Gradient**



**Fundamental observation**: Given any in-plane stress variation dependent only on y, there are no stresses acting on interface in the interior of a film or multlayer.

--An interior interface crack has zero stress intensity

#### What can produce x-dependence and stress intensity?

- --- proximity to a free edge or through-crack
- --- buckling of film due to compressive stress
- --- thermal gradient and low conductivity across crack

#### Isolated interface crack in a thermal gradient

Stress difference in central region of a long crack (cracked - uncracked): The stress difference produces the crack tip intensities

$$\Delta \sigma = \frac{E_1}{1 - \nu_1} \alpha_1 \Delta T \left( 1 - y / h \right), \quad \Delta T \equiv T_i - T_0 = \frac{T_s - T_0}{1 + B}$$

Biot number for interface:

$$B = \frac{c_i h}{k_1}$$
, heat flow  $= q = -c_i (T_i - T_0)$ 

Thermal conductivity in top layer

Interface thermal conductivity





Basic loading involving the difference between the cracked & uncracked configurations

Basic solution gives:

$$\Delta P = \frac{1}{2} \frac{E_1 h \alpha_1 \Delta T}{(1 - \nu_1)}, \quad \Delta M = -\frac{1}{12} \frac{E_1 h^2 \alpha_1 \Delta T}{(1 - \nu_1)}$$
$$G = \frac{1}{6} \left( \frac{1 + \nu_1}{1 - \nu_1} \right) E_1 h \left( \alpha_1 \left( T_i - T_0 \right) \right)^2$$
$$\psi = \tan^{-1} \left( \frac{\sqrt{3} \tan \omega + 1}{\sqrt{3} - \tan \omega} \right) = 82^\circ \quad (\omega = 52.1^\circ)$$

- G is small even with B=0 compared with result for edge crack.
- This is the long crack limit. It is an upper bound for shorter cracks.
- The crack tip experiences near mode II conditions

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#### Thermal Barrier Coatings Subject to Temperature Gradient: Interface Delamination on Cool-down





At highest operating temperature—stresses relax to zero

At any stage during cool-down—stress is thermo-elastic (no relaxation)

$$\Delta T_{sub} = T_{sub}^{i} - T_{sub}$$

$$\Delta T_{sur} = T_{sur}^{i} - T_{sur}$$

$$\Delta T_{sur/sub} = \Delta T_{sur} - \Delta T_{sub}$$

$$\Delta \sigma = \frac{E_{1}\alpha_{tbc}\Delta T_{sur/sub}}{(1 - \nu_{1})} \left(1 + \frac{y}{h}\right)$$

*pg*.10

$$+\frac{E_1 \Delta \alpha \Delta I_{sub}}{(1-V_1)}, \quad \Delta \alpha = \alpha_{sub} - \alpha_{tbc}$$

**Basic solution gives:** 

$$G = \frac{(1+\nu_2)E_1h}{6(1-\nu_2)} \left( \left( \alpha_{tbc} \Delta T_{sur/sub} \right)^2 - 3\alpha_{tbc} \Delta T_{sur/sub} \Delta \alpha \Delta T_{sub} + 3\left( \Delta \alpha_{tbc} \Delta T_{sub} \right)^2 \right)_{10}$$

$$\tan \psi = \frac{\sqrt{3} \tan \omega \left( \alpha_{tbc} \Delta T_{sur/sub} - 2\Delta \alpha \Delta T_{sub} \right) - \alpha_{tbc} \Delta T_{sur/sub}}{\sqrt{3} \left( \alpha_{tbc} \Delta T_{sur/sub} - 2\Delta \alpha \Delta T_{sub} \right) + \tan \omega \alpha_{tbc} \Delta T_{sur/sub}}$$

$$8$$

Interface toughness (see earlier slide):

$$\Gamma_{C}(\psi) = \Gamma_{IC} \left( 1 + \tan^{2}((1-\lambda)\psi) \right)$$

$$G = \Gamma_{C}(\psi) \implies Y^{2} - 3YX + 3X^{2} = 6\left( 1 + \tan^{2}\left((1-\lambda)\psi\right) \right)$$

$$X = \frac{\Delta\alpha\Delta T_{sub}}{\sqrt{\frac{(1-\nu_{1})}{(1+\nu_{1})}}}, \quad Y = \frac{\alpha_{tbc}\Delta T_{sur/sub}}{\sqrt{\frac{(1-\nu_{1})}{(1+\nu_{1})}}}$$



#### Buckle Delaminations: Interface cracking driven by buckling Three Morphologies: Straight-sided, Varicose and Telephone Cord





#### Experimental observations 200nm DLC film on silicon



Propagation of a buckle delamination along a prepatterned tapered region of low adhesion between film and substrate. In the wider regions the telephone cord morphology is observed. It transitions to the straight-sided morphology in the more narrow region and finally arrests when the energy release rate drops below the level needed to separate the interface.



Energy-release rate can also be obtained from direct energy change calculation

Mode mix depends on the amplitude of The buckle

Plots are given on next overhead

pg.13 Energy release rate and mode mix on sides of Straight-sided buckle delamination





#### Inverse determination of interface toughness, stress (or modulus) by measuring buckling deflection and delamination width

#### Straight-sided delamination without ridge crack on flat substrate



front (SS)

The basic results can be written as:

S ~ stretching stiffness  $D \sim bending \ stiffness$ 

$$G_{SS} = \frac{1}{2} S \left(\frac{\pi}{4} \frac{\delta}{b}\right)^4$$
$$G_{side} = \frac{1}{2} S \left(\frac{\pi}{4} \frac{\delta}{b}\right)^4 + 2D \left(\frac{\pi}{b}\right)^2 \left(\frac{\pi}{4} \frac{\delta}{b}\right)^2$$
$$N_0 = D \left(\frac{\pi}{b}\right)^2 + S \left(\frac{\pi}{4} \frac{\delta}{b}\right)^2$$

Applies to any multilayer film with arbitrary stress distribution

If bending and stretching stiffness of the film are known, then the energy release rates and the resultant pre-stress can be determined by measurement of the deflection and the delamination width.

If resultant pre-stress is known, then the equations can be used to determine film modulus and release rates in terms of deflection and delamination width- see Faulhaber, et al (2006) for an example.

# Metal or Ceramic Films on Compliant Substrates (Polymer or Elastomer) pg.15

Cotterell & Chen, 2000; Yu & Hutch, 2002; Parry, et al., 2005

Analytical Fact: Edges of buckle delamination is effectively clamped if substrate modulus is larger than 1/3 of film modulus (i.e. clamped plate model is valid)

Highly compliant substrate has three effects:

- 1) Stabilizes straight-sided buckle delamination and tends to eliminate telephone cord morphology.
- 2) Significant film rotation occurs at edges of delamination and larger buckling deflections.
- 3) Relaxation of stress along bonded edges of delamination (shear lag effect) amplifies energy released.



# **Energy Released as a Function of Morphology**

(a)

(b)



Telephone cord morphology has lowest energy and releases the most energy/area.

*pg*.16

## Real Time Propagation of a Telephone Cord buckle Delamination

M.-W. Moon



*pg*.17



**Conclusion:** A compliant substrate (or even one with no mismatch) reduces the possibility of delamination initiating at the edge when a film extends to the edge of a substrate. The crack has to be ten times the film thickness, depending on the elastic mismatch, to attain steady-state.

If the film terminates in the interior of the substrate, there is no protection—the crack only has to be about ½ times the film thickness to reach steady state.



*pg*.19

W

α<sub>D</sub>=0.9

30

40

h

v<sub>r</sub>=0.3

 $\Lambda_{B}$ 

20

w/h

10

0.75

0.5

0.25

0

0

ĀVAB

#### **3D Effects for Delamination of Thin Film Strips**

Energy/area stored in infinitely wide film subject to equi-biaxial thermal mismatch strain

$$\Lambda_{B} = \frac{(1 - v_{1})\sigma^{2}h}{E_{1}} = \frac{E_{1}}{(1 - v_{1})} (\Delta \alpha \Delta T)^{2} h$$

Energy/area stored in a very narrow film strip subject to equi-biaxial thermal mismatch strain

$$\Lambda_{U} = \frac{\sigma^{2}h}{2E_{1}} = \frac{1}{2}E_{1}\left(\Delta\alpha\Delta T\right)^{2}h$$
 1D, no constraint perpendicular to strip

Average energy/area stored in infinitely long strip of width w subject to an equi-biaxial thermal mismatch strain. Even with no mismatch, the average energy is only 90% of that for an infinitely wide strip when w/h=50. If the substrate is very compliant the value may only slightly above the very narrow strip limit even when w/h=50.

Steady-state energy release rate for strip delamination  $a>>h\colon G_{\rm SS}=\Lambda$ 



# DELAMINATION MECHANICS Supplementary Notes and References

Page numbers refer to the slide page. A limited reference list is given on the last page.

cover some of the basic aspects in an assessable manner. It is assumed that the reader has a basic familiarity with fracture mechanics. Aspects of interface fracture mechanics are Much of the mechanics outlined in the slides was developed around 1990 and is Hutchinson and Wei (1995). For the student first getting acquainted with delamination mechanics, the notes, "Mechanics of thin films and multilayers", by Hutchinson (1996) Two other basic references important in the developments, and if the author is not acquainted with this subject it with emphasis on interfaces are those by Evans and Hutchinson (1995) and Evans might be good to start with Section II.C of Hutchinson and Suo (1990) summarized in the article by Hutchinson and Suo (1992).

the past few years. References are provided. It should be noted that the references listed The slides also cover topics, in particular, extensions and applications, studied in on the last page are not intended to be comprehensive—they are primarily those of the contributors and to the wider literature. The book on thin films by Freund and Suresh Page 1. This side provides a pictorial overview of the types of problems considered author and his colleagues. These references will permit the reader access to other (2003) also provides excellent coverage of some delamination topics.

-see the notes by Suo and Hutchinson (1990). The examples in the slides are all based on the limiting case The shown where the layer below the interface is very thick compared to the layer (or layers) results from this solution derive elementary energy accounting. The relative proportion layers with differing moduli and Poisson's ratios has many applications. Dundurs' two Hutchinson (1996). One reason for the usefulness and robustness of the energy release of mode II to mode I, as measured by  $\psi$  , requires a the full elasticity solution given by dimensionless elastic mismatch parameters characterize the solution: in the slides they Page 2. The two-layer elasticity solution of Suo and Hutchinson (1990) for isotropic have been given for planes strain. Refer to the literature for plane stress definitions. energy release rate can be obtained by simple methods simply by accounting for the above the interface, and the limit is for an infinitely deep layer below the interface difference between the energy well ahead and well behind the crack tip-

singularity field characterizing the behavior near the tip of an interface have precisely the If the second Dundurs mismatch parameter,  $\beta_D$ , is zero, the stresses in the same form as in the homogeneous case with

$$\sigma_{\alpha\beta} = K_I \sqrt{\frac{1}{2\pi r}} f_{\alpha\beta}^I(\theta) + K_I \sqrt{\frac{1}{2\pi r}} f_{\alpha\beta}^I(\theta)$$

are the same as those for the homogeneous material. If  $\beta_D$  is not zero, the stresses captures most of the essential features of the phenomena of interest. Students interested where r and  $\theta$  are planar polar coordinated centered at the tip. The functions  $f^{I}$  and singularity. In all the examples considered in the slides we will take  $\beta_D = 0$  since this –a so-called oscillatory in pursuing the effect of non-zero  $\beta_D$  can start off by looking at Section II. Page 3. This is the basic result which will be used throughout the slides associated with the crack tip singularity are more complicated-

Page 4. To see the effect of friction on the mode II edge delamination crack see the reference by Balint and Hutchinson (2001)

substrates such as metals on polymers) have not been published and do not appear to be Page5. Results for  $\omega(\alpha_p)$  for  $\alpha_p$  near unity (i.e. for stiff films on very compliant available

Page 6. See Evans and Hutchinson (1995) and Evans, Hutchinson and Wei (1999) for discussion of interface toughness and other systems

Page 8. Reference on delamination in presence of temperature and stress gradients Evans and Hutchinson (2006) Page 9. The basic solution for an isolated crack in a homogeneous material subject to a Hutchinson and Evans (2002) and Evans and Hutchinson (2006) for work specifically temperature gradient was given by Sih (1962). See Hutchinson and Lu (1995) related to temperature gradients and their role in delamination of coatings Page 10. Reference: Evans and Hutchinson (2006)

theoretical and experimental aspects. Basic mechanics covered in the slides is given in Hutchinson and Suo (1992), Section VI, and Hutchinson, Thouless and Liniger (1992). Page 11-13. There is now a large literature on buckling delamination covering both

More recent references are Moon et al. (2002) and Moon et al (2004); additional references are cited in these papers

to delamination of thermal barrier coatings on curved substrates. The approach has also Page 14. This approach has been developed in Faulhaber et al. (2006) with application been extended in this paper to delaminations with ridge cracks.

stiff films on polymeric substrates have been published in Cotterell & Chen (2000) Yu & Page 15. Theoretical and experimental work for straight-sided buckle delaminations for Hutchinson (2002); Parry et al. (2005)

Page16. The reference for this slide is Moon et al. (2004).

Page 17. The movie of the real time evolution of a buckle delamination was supplied by M-Y. Moon. See the work of A. Volinsky for many interesting examples of buckle delamination.

Page 19. Three-dimensional results for delamination of thin film strips are presented in Page 18. These and other related results are given by Yu, He and Hutchinson (2001). Yu and Hutchinson (2003)

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